

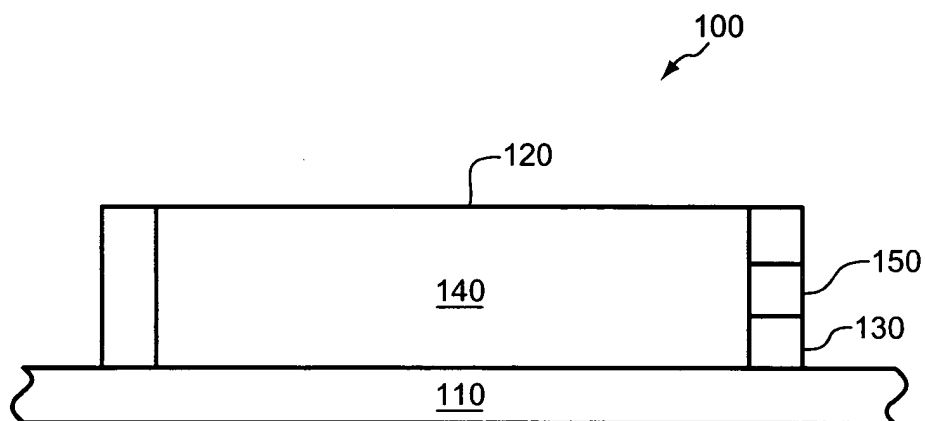


Title: "Purging Gas from a Photolithography Enclosure Between a Mask Protective Device and a Pattern Mask"

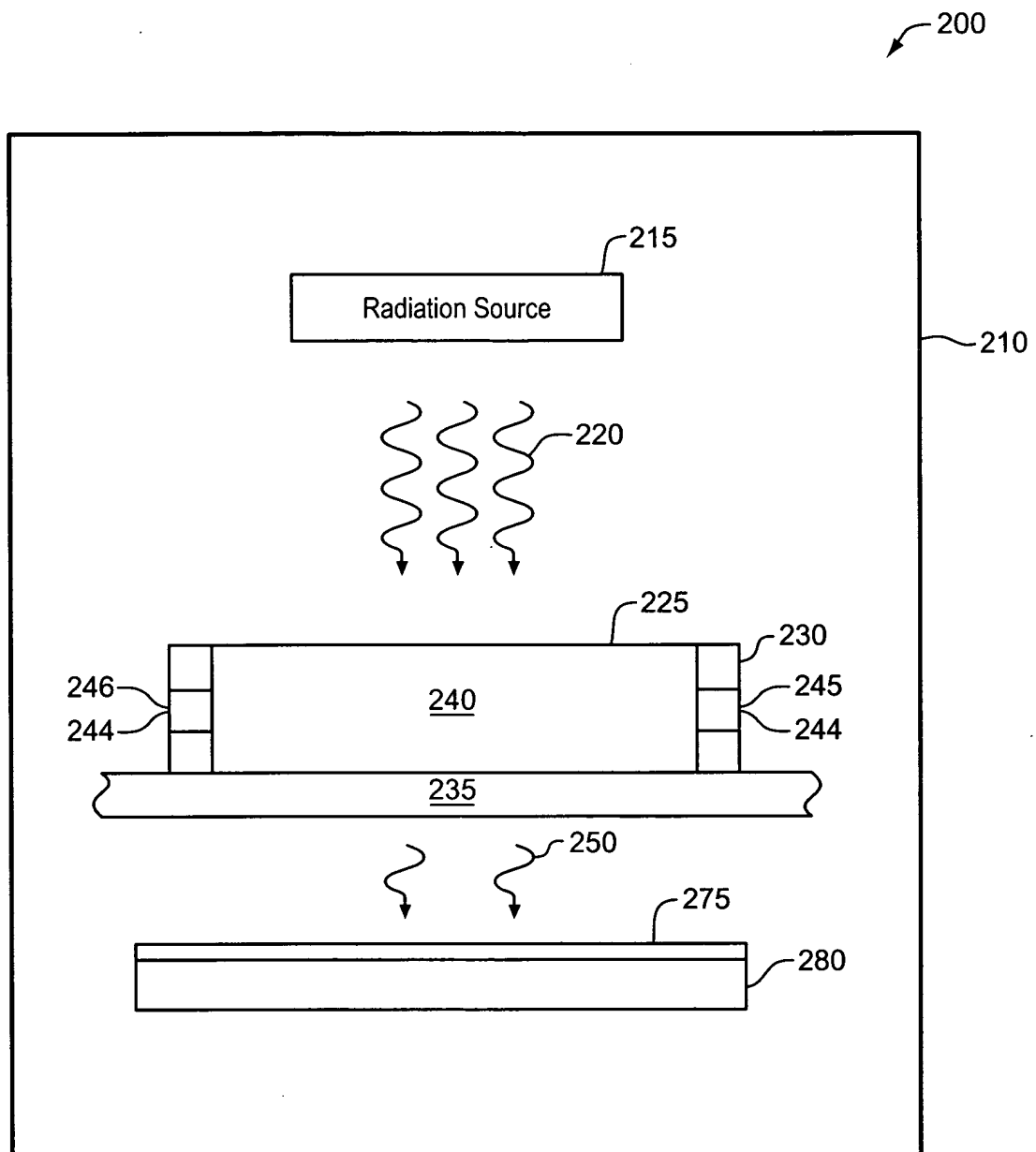
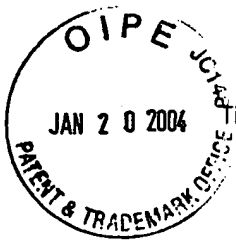
Inventors: Han-Ming Wu et al. Application No.: 09/752,938 Docket No.: 42P10058

Blakely, Sokoloff, Taylor & Zafman 303-740-1980

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**FIG. 1**  
**PRIOR ART**



**FIG. 2**



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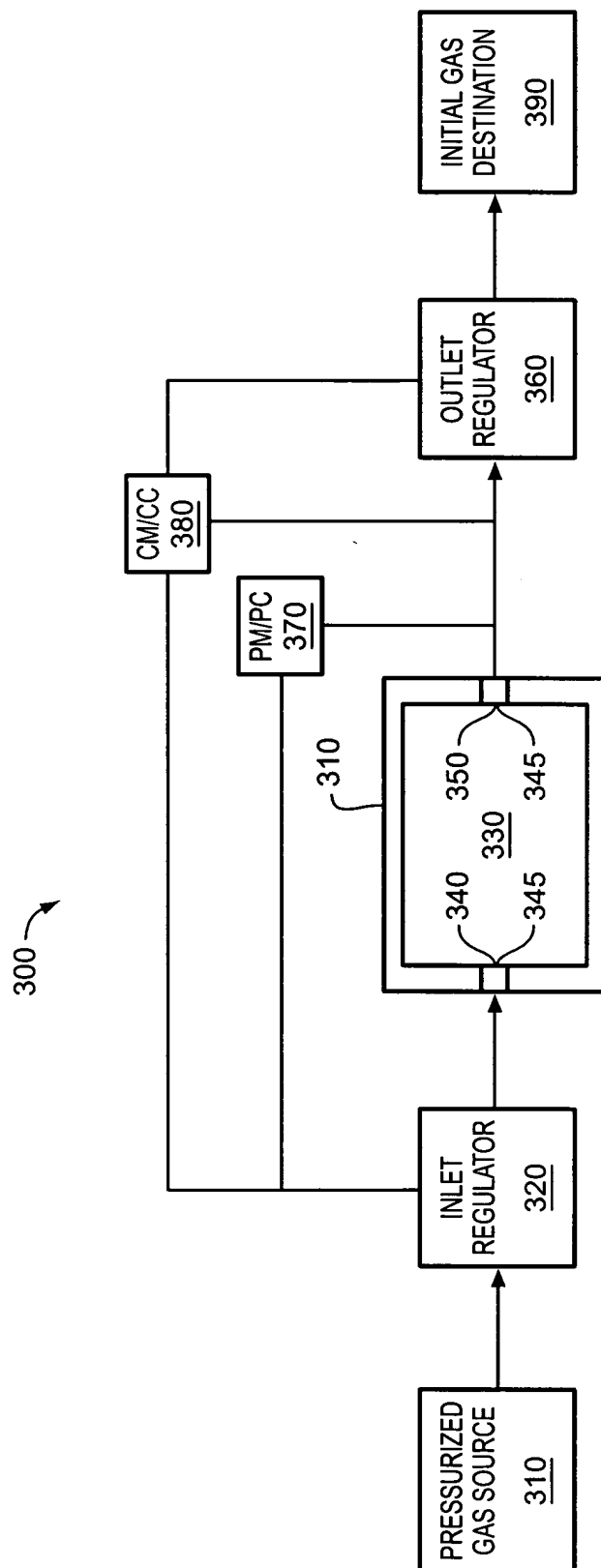
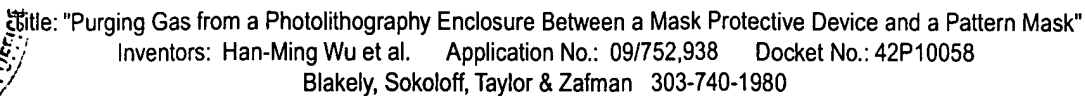
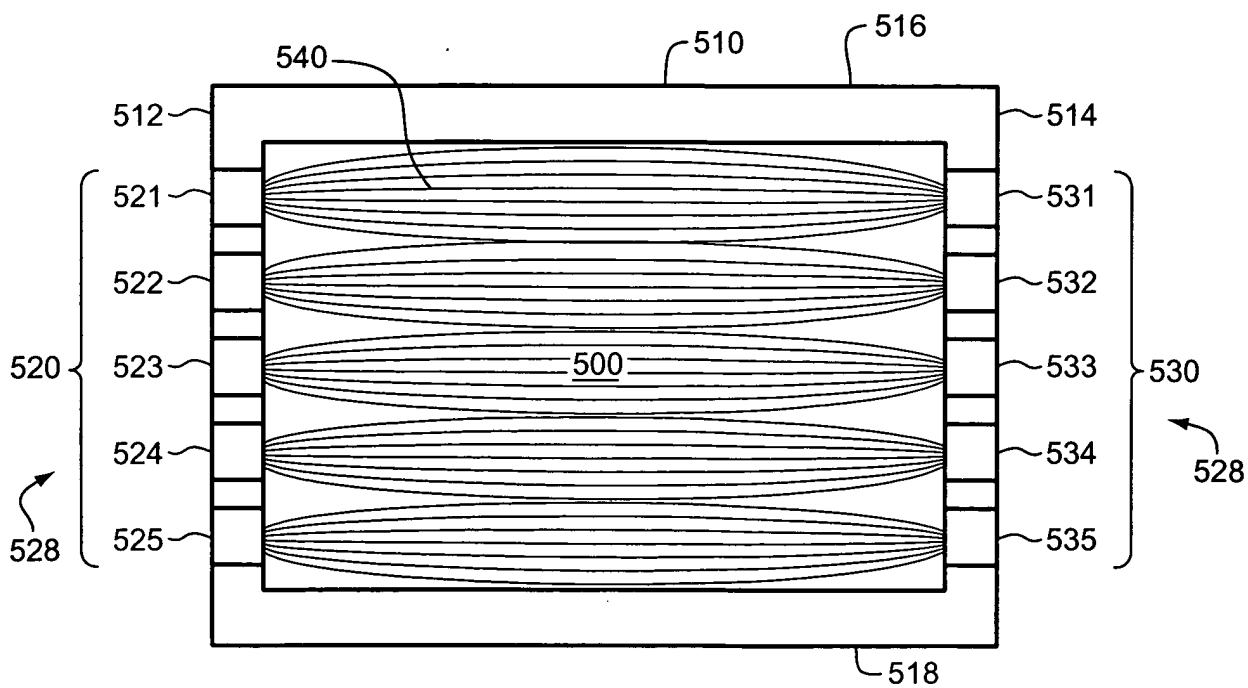
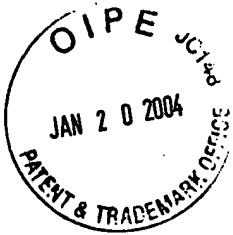


FIG. 3



**FIG. 4**





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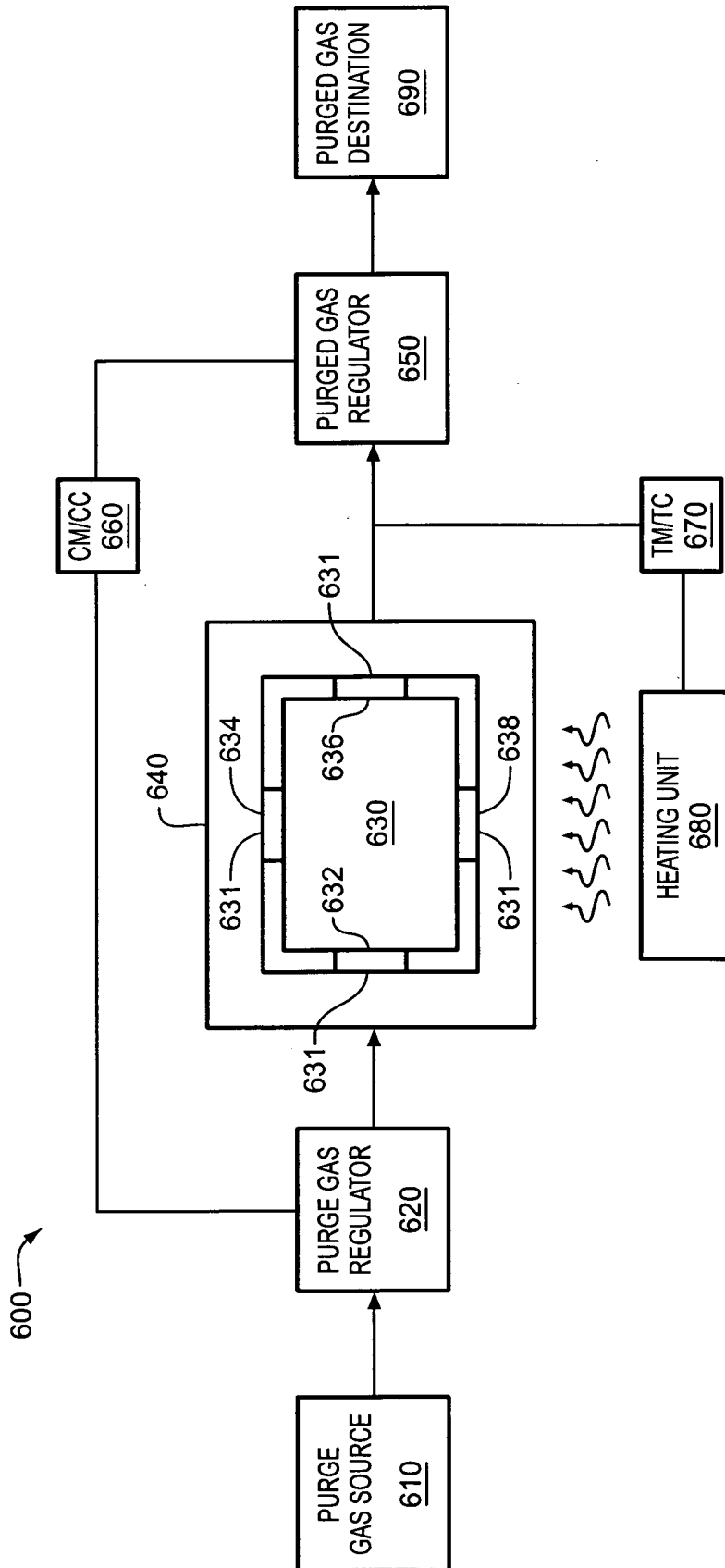


FIG. 6

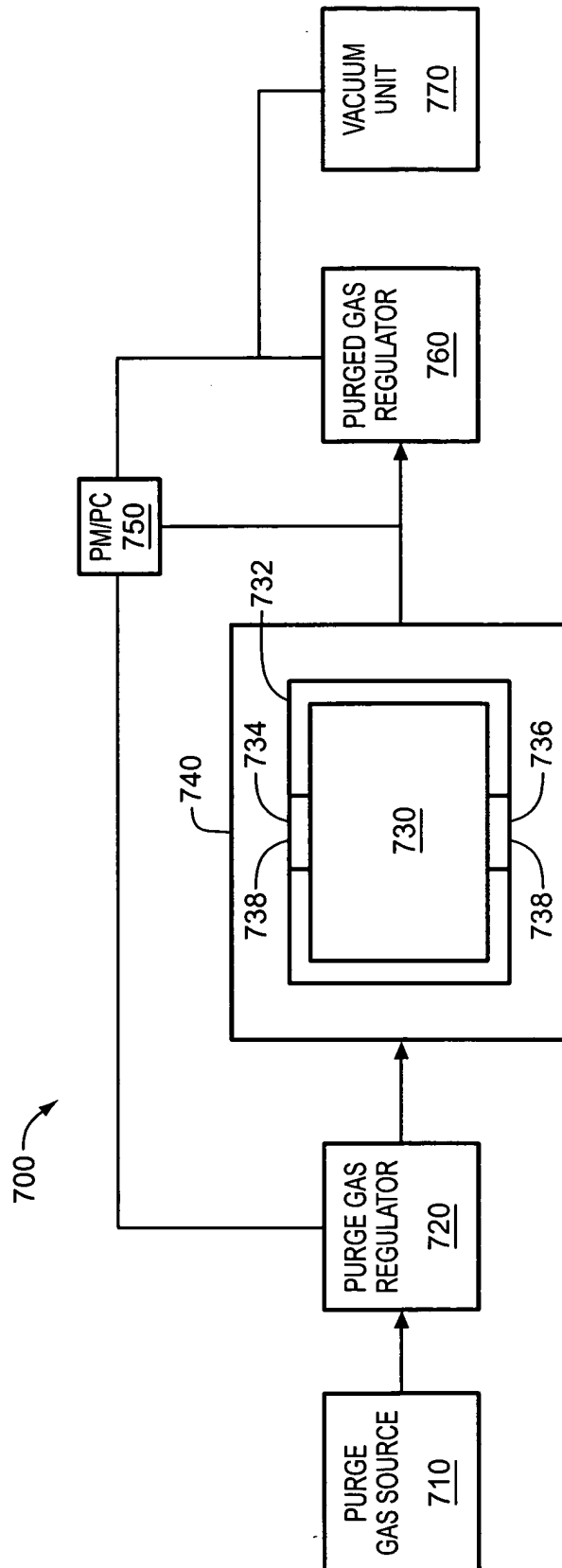


FIG. 7



**FIG. 8**

